	Туре	Hits	Search Text	DBs	Time Stamp
P	BRS	389	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with maintenance\$1 with manag\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/10/28
N	BRS	1178		US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/10/28 15:19
ω	BRS	0	(700/12,14,17,19,108,117,1 21,174,175,176,178,180.ccl s.) and semiconductor\$1 same process\$3 with parameter\$1 and prevent\$3 with maintenance\$1 and (validat\$3 or evaluat\$3 or estimat\$3) with tim\$3 with cost\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/10/28 15:19
4.2	BRS	65	onductor\$1 or 1 or chip\$1 or die\$1 1 or (integrated adj t\$1)) with product\$1 ualit\$3 and ction\$1 or status or 1) with equipment\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT;	2005/10/28

Туре	e Hits	Search Text	DBs	Time Stamp	Comments
<b>5</b> BRS	Ó	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with product\$1 with qualit\$3 and (condiction\$1 or status or state\$1) with equipment\$1 and (estimat\$3 or validat\$3 or evaluat\$3 or predict\$3) with qualit\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/10/28	
6 BRS	o)	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with product\$1 with qualit\$3 and (condiction\$1 or status or state\$1) with equipment\$1 with parameter\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/10/28 15:30	

	Туре	Hits	rch Tex	DBs	<u> </u>
7 E	BRS 0	·	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with product\$1 U with qualit\$3 and (condiction\$1 or status or state\$1) with equipment\$1 I with parameter\$1 and process\$3 with parameter\$1 and equipments	US-P USPA JPO; IBM_	US-PGPUB; USPAT; EPO; 2005/10/28 JPO; DERWENT; 15:30 IBM_TDB
ω	BRS 8		\$1 or die\$1 p\$1 or die\$1 tegrated adj th product\$1 and or status or equipment\$1	US-P( USPA) JPO; IBM_]	US-PGPUB; USPAT; EPO; 2005/10/28 JPO; DERWENT; 15:30 IBM_TDB
9	BRS	б 5	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with product\$1 with qualit\$3 and (condiction\$1 or status or	S S S S S S S S S S S S S S S S S S S	US-PGPUB; USPAT; EPO; 2005/10/28 JPO; DERWENT; 15:31 IBM_TDB

13.	12 H	
BRS	BRS.	Туре
	17	Hits
(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adjcircuit\$1)) with product\$1 with qualit\$3 and (condiction\$1 or status or state\$1) with equipment\$1 and database\$1 and (record\$3 or stor\$3 or sav\$3) and (predict\$3 or validat\$3 or evaluat\$3) and equipment\$	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with product\$1 with qualit\$3 and (condiction\$1 or status or state\$1) with equipment\$1 and database\$1 and (record\$3 or stor\$3 or sav\$3) and (predict\$3 or inspect\$3 or estimat\$3 or validat\$3 or evaluat\$3)	Search Text
US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	DBs
2005/10/28 15:34	2005/10/28	Time Stamp
	·	Comments

	Туре	Hits	Search Text	DBs	Time Stamp	Comments
<b>1 4</b>	BRS	9 .	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with qualit\$3 and (condiction\$1 or status or state\$1) with equipment\$1 and database\$1 and (record\$3 or stor\$3 or sav\$3) and (predict\$3 or validat\$3 or evaluat\$3) and equipment\$	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/10/28 15:35	
15 E	BRS	76	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with qualit\$3 and (record\$3 or stor\$3 or sav\$3 or database) with equipment with (parameter\$1 or measur\$6)	US-PGPUB; USPAT; EPO; UPO; DERWENT; IBM_TDB	2005/10/28 15:36	

17	1 6	
7 BRS	BRS	Туре
24	Η Ω	Hits
(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adjcircuit\$1)) with qualit\$3 and (record\$3 or stor\$3 or sav\$3 or database) with equipment with (parameter\$1 or measur\$6) and (record\$3 or stor\$3 or sav\$3 or database) with process\$3 with (parameter\$1 or measur\$6) and (compar\$4 or differen\$2) with equipment\$1	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adjcircuit\$1)) with qualit\$3 and (record\$3 or stor\$3 or sav\$3 or database) with equipment with (parameter\$1 or measur\$6) and (record\$3 or stor\$3 or sav\$3 or database) with process\$3 with [parameter\$1 or measur\$6]	Search Text
US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	DBs
2005/10/28	2005/10/28	Time Stamp
		Comments

20	19	
BRS	BRS	Туре
42	2	Hits
(record\$3 or stor\$3 or sav\$3 or database) with equipment with (status\$2 or condition\$1 or state\$1) and (inspect\$3 or evaluat\$3 or estimat\$3 or validat\$3) with test\$3 with (semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adjcircuit\$1)) with product\$1 and (analyz\$3 or analys\$3)	(record\$3 or stor\$3 or sav\$3 or database) with equipment with (status\$2 or condition\$1 or state\$1) and (inspect\$3 or evaluat\$3 or estimat\$3 or validat\$3) with test\$3 with (semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adjcircuit\$1)) with product\$1 and statistic\$4 with (analyz\$3 or analys\$3)	Search Text
US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	DBs
2005/10/28	2005/10/28	Time Stamp
		Comments

н	Туре	Hits	Search Text	DBs	Time Stamp	Comments
<b>23</b> BI	BRS	ω	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with qualit\$3 with product\$1 and t-test\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/10/28	
24 BI	BRS	18	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with maintenance\$1 with manag\$6 and optimiz\$5 with performance	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/10/28 15:13	
25 B	BRS	32542	<pre>(determin\$3 or detect\$3 or monitor\$3) with (semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with (defect\$1 or error\$1 or fail\$4 or malfunction\$2 or anomal\$3 or problem\$1)</pre>	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/10/28 15:15	

<b>27</b> BI	<b>26</b> BI	н
BRS	BRS	Туре
0	18	Hits
(determin\$3 or detect\$3 or monitor\$3) with (semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adjcircuit\$1)) with (defect\$1 or error\$1 or fail\$4 or malfunction\$2 or anomal\$3 or problem\$1) and select\$3 with process\$3 with parameter\$1 same optimiz\$3 with qualit\$3 with performance\$1 with	(determin\$3 or detect\$3 or monitor\$3) with (semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adjcircuit\$1)) with (defect\$1 or error\$1 or fail\$4 or malfunction\$2 or anomal\$3 or problem\$1) and optimiz\$3 with qualit\$3 with performance\$1 with product\$1	Search Text
US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	DBs
2005/10/28 15:18	2005/10/28	Time Stamp
		Comments

	Туре	Hits	Search Text	DBs	Time
28	BRS	2032	702/176,177,178,183,184,18 t	US-PGPUB; USPAT; EPO JPO; DERWE IBM TDB	US-PGPUB; USPAT; EPO; 2005/10/28 JPO; DERWENT; 15:20 IBM_TDB
29	BRS	5714	(700/12,14,17,19,108,117,1 21,174,175,176,178,180.cc1 s.)	US-PGPUB; USPAT; EP JPO; DERW	US-PGPUB; USPAT; EPO; 2005/10/28 JPO; DERWENT; 15:19 IBM_TDB
30	BRS	7637	702/176,177,178,183,184,18 7.ccls.or 700/12,14,17,19,108,117,12 1,174,175,176,178,180.ccls	US-PGPUB; USPAT; EPO JPO; DERWE IBM_TDB	US-PGPUB; USPAT; EPO; 2005/10/28 JPO; DERWENT; 15:23 IBM_TDB
31	IS&R	2	("6745094").PN.	US-PGPU USPAT; JPO; DE IBM_TDB	US-PGPUB; USPAT; EPO; 2005/10/28 JPO; DERWENT; 15:22 IBM_TDB
32	BRS	0	"6745094".uref.	US-PGPUB; USPAT; EP JPO; DERW IBM IDB	US-PGPUB; USPAT; EPO; 2005/10/28 JPO; DERWENT; 15:23 IBM_TDB

	Туре	Hits	Search Text	DBs	Time Stamp	Comments
<b>ω</b>	BRS	94	(702/176,177,178,183,184,187.ccls. or 700/12,14,17,19,108,117,121,174,175,176,178,180.ccls.) and (determin\$3 or detect\$3 or monitor\$3) with (semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adjcircuit\$1)) with (defect\$1 or error\$1 or fail\$4 or malfunction\$2 or anomal\$3 or problem\$1)	US-PGPUB	2005/10/28	
<b>S</b>	BRS	74	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with product\$1 with qualit\$3 and (condiction\$1 or status or state\$1) with equipment\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/10/28 15:29	

	Туре	Hits	Search Text	DBs	Time Stamp	Comments
37	BRS	7	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with product\$1 with qualit\$3 and (condiction\$1 or status or state\$1) with equipment\$1 and (estimat\$3 or validat\$3 or evaluat\$3 or predict\$3) with qualit\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/10/28	
38	BRS	7	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with product\$1 with qualit\$3 and (condiction\$1 or status or state\$1) with equipment\$1 with parameter\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/10/28	

	Туре	Hits	Search Text	DBs	Time Stamp	Comments
3 9	BRS	0	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adjcircuit\$1)) with product\$1 with qualit\$3 and (condiction\$1 or status or state\$1) with equipment\$1 with parameter\$1 and process\$3 with parameter\$1 and equipments	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/10/28 15:30	
40	BRS	6	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with product\$1 with qualit\$3 and (condiction\$1 or status or state\$1) with equipment\$1 and equipments	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/10/28 15:30	·
41	BRS	74	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with product\$1 with qualit\$3 and (condiction\$1 or status or state\$1) with equipment\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/10/28 15:31	

Туре	Hits	(1)	DBs	ω
<b>42</b> BRS	26	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with product\$1 with qualit\$3 and (condiction\$1 or status or state\$1) with equipment\$1 and database\$1	US-PGPUB; USPAT; EPO; JPO; DERWEN IBM_TDB	3; EPO; 2005/10/28 RWENT; 15:31
<b>43</b> BRS		(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with product\$1 with qualit\$3 and (condiction\$1 or status or state\$1) with equipment\$1 and database\$1 and (record\$3 or stor\$3 or sav\$3) with measur\$6	US-PGPUB; USPAT; EPO; JPO; DERWEN IBM_TDB	JB; EPO; 2005/10/28 ERWENT; 15:32

<b>4</b> 5	44	
BRS	BRS	Type
C	25	Hits
uctor\$1 or r chip\$1 or r (integrate)) with prodit\$3 and on\$1 or stat with equipme ase\$1 and or stor\$3 od (predict\$3 or estimat\$ or evaluat\$ ments	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adjcircuit\$1)) with product\$1 with qualit\$3 and (condiction\$1 or status or state\$1) with equipment\$1 and database\$1 and (record\$3 or stor\$3 or sav\$3) and (predict\$3 or inspect\$3 or estimat\$3 or validat\$3 or evaluat\$3)	Search Text
US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	DBs
2005/10/28	2005/10/28	Time Stamp
		Comments

47	46	
BRS	BRS	Type
10	10	Hits
(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adjcircuit\$1)) with qualit\$3 and (condiction\$1 or status or state\$1) with equipment\$1 and database\$1 and (record\$3 or stor\$3 or sav\$3) and (predict\$3 or validat\$3 or evaluat\$3) and equipments	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adjcircuit\$1)) with qualit\$3 and (condiction\$1 or status or state\$1) with equipment\$1 and database\$1 and (record\$3 or stor\$3 or sav\$3) and (predict\$3 or validat\$3 or estimat\$3 or validat\$3 or evaluat\$3) and equipments	Search Text
US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	DBs
2005/10/28	2005/10/28	Time Stamp
		Comments

50	
BRS	Туре
29	Hits
(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adjcircuit\$1)) with qualit\$3 and (record\$3 or stor\$3 or sav\$3 or database) with equipment with (parameter\$1 or measur\$6) and (record\$3 or stor\$3 or sav\$3 or database) with process\$3 with (parameter\$1 or measur\$6) and (compar\$4 or differen\$2) with equipment\$1	Search Text
US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	DBs
2005/10/28	Time Stamp
	Comments

51 BRS	17
	Туре
19	Hits
(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with qualit\$3 and (record\$3 or stor\$3 or sav\$3 or database) with equipment with (parameter\$1 or measur\$6) and (record\$3 or stor\$3 or sav\$3 or database) with process\$3 with (parameter\$1 or measur\$6) and (compar\$4 or differen\$2) with	. Search Text
US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	DBs
2005/10/28	Time Stamp
	Comments

<b>53</b> BRS	<b>52</b> BRS	Туре
U		e Hits
or data witter ects ects or icons con icon	(record\$3 or stor\$3 or sav\$3 or database) with equipment with (status\$2 or condition\$1 or state\$1) and (inspect\$3 or evaluat\$3 or estimat\$3 or validat\$3) with test\$3 with (semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adjcircuit\$1)) with product\$1 and statistic\$4 with (analyz\$3 or analys\$3)	Search Text
US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	DBs
2005/10/28	2005/10/28 15:37	Time Stamp
	·	Comments

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		. 7
BRS	BRS	Туре
17	. 2	Hits
(record\$3 or stor\$3 or sav\$3 or database) with equipment\$1 with (status\$2 or condition\$1 or state\$1) and (inspect\$3 or evaluat\$3 or predict\$3) with (semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adjcircuit\$1)) with product\$1 and (analyz\$3 or analys\$3) and statistic\$4	(record\$3 or stor\$3 or sav\$3 or database) with equipment\$1 with (status\$2 or condition\$1 or state\$1) and (inspect\$3 or evaluat\$3 or estimat\$3 or validat\$3 or predict\$3) with (semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adjcircuit\$1)) with product\$1 and (analyz\$3 or analys\$3)	Search Text
US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	DBs
2005/10/28	2005/10/28	Time Stamp
		Comments

	Туре	Hits	Search Text	DBs	Time
5	BRS	9	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adj circuit\$1)) with qualit\$3 with product\$1 and t-test\$3	US-PGPUB; USPAT; EPO JPO; DERWE IBM_TDB	); 2005/10/28 3NT; 15:40
57	BRS	4	onductor\$1 or 1 or chip\$1 or die\$1 1 or (integrated adj t\$1)) with qualit\$3 roduct\$1 and t- and process\$3 with ter\$1	US-PGPUB; USPAT; EPO JPO; DERWE:	; PO; 2005/10/28 WENT; 15:40
58	BRS	0	(semiconductor\$1 or wafer\$1 or chip\$1 or die\$1 or IC\$1 or (integrated adjcircuit\$1)) with qualit\$3 with product\$1 and t-test\$3 and process\$3 with parameter\$1 and optimiz\$3	US-PGPUB; USPAT; EPO JPO; DERWE IBM_TDB	IB; EPO;  2 RWENT;  1

	U	Ъ	Document ID	Issue Date	Page s	Title	Current OR	Current XRef	Retrieva 1 Classif
н			US 2005020365 4 · A1	20050915	18	System and method for scheduling manufacturing jobs for a semiconductor manufacturing tool	700/100	700/108	700/108
8	×		US 2005019772 8 A1	20050908		FEATURE TARGETED INSPECTION	700/110	700/121	700/121
	×		US 2005017726 9 A1	20050811	26	Method for dynamic sensor configuration and runtime execution	700/121		700/121
42	×		US 2005017726 3 A1	20050811		System and method for monitoring wafer furnace production efficiency	700/108		700/108
ហ	×		US 2005017162 7 A1	20050804		Method and apparatus for monitoring tool performance	700/121		700/121
<u>o</u>	×		US 2005017162 6 A1	20050804		System, method, and medium for monitoring performance of an advanced process control system	700/108		700/108

	а	н	Document ID	Issue Date	Page s	Title  Method and apparatus	Current	Current XRef	Retrieva 1 Classif
7	×		US 2005015991 20050721 1 A1	20050721		and apparat tomatic sens lation	us or 702/104	700/121	700/121
œ	×		US 2005013773 7 A1	20050623		Integrated circuit card system and application loading method	700/121		700/121
9	×		US 2005012509 0 A1	20050609		Method and apparatus for evaluating processing apparatus status and predicting processing result	700/108	438/14; 700/121	700/108;
10	. 🗙		US 2005012251 0 A1	20050609		System and method for process variation monitor	356/237.2 382/145; 700/121	382/145 <b>;</b> 700/121	700/121
11	×		US 2005009092 3 A1	20050428		Method for monitoring a batch system	700/109	257/E21.5 25; 700/121	700/121

Current Current XRef 38/14

		Н	ID	Date	ທູ	Title	OR	XRef	)   L
									CLASSII
						Algorithms tunning for dynamic lot		700/100;	
16	×		2005007103 1 A1	20050331		batching in wafer	700/101	700/121	700/121
			110			System and methed			
17	₹		) ) ) ) ) ) ) ) )	20050310		fective field	700/110	700/121	700/131
F	->			7000010		loss analysis for			,00/ +/ +
						semiconductor wafers			
						Methods for			
						detecting			
			110			transitions of wafer			
χ	< −	_	005005406 00050310	20050310		surface properties	<u> </u>	700/121	700/121
ŀ	>		2000000120	70000010			1 ( H / C	100/ + 2 +	171/00/
						mechanical polishing			•
						for process status			
						and control			
						Non-invasive system			
	<del></del>		110			and method for			
5	₹			300E0303		diagnosing potential	703/103		700/100
1	>		71	2000000		ns of	102/100		102/TO3
			17.			semiconductor			
						equipment components			

_	24 X	23 X	22 X	21 X X	20 X	U 1
SU	US 2005001089 0 A1	US 2005002738 8 A1	US 2005002748 2 A1	US 2005003854 4 A1	US 2005004974 0 A1	Document ID
20011222	20050113	20050203	20050203	20050217 7	20050303	Issue Date
51	22					Page s
Processing method and processing	Design-based monitoring	ing etrically ited film ed registration	Method for estimating the quality of wood chips	ᆈ	Method, system and program product providing a configuration specification language having clone latch support	Title
700/121	716/19	700/121	702/183	700/108	700/121	Current OR
	700/121; 716/21; 716/4			700/121; 700/80		Current XRef
700/121	700/121	700/121	702/183	700/108; 700/121	700/121	Retrieva 1 Classif

	ū	ш	Document ID	Issue Date	Page s	Title	Current OR	Current XRef	Retrieva 1 Classif
26	×		US 2004025476 20041216 1 A1	20041216	,	Operation monitoring method for treatment apparatus	702/182	702/183	702/183
27	×		US 2004025466 9 Al	20041216		Automatic recognition of locator die in partial wafermap process	700/121	382/151	700/121
N 80	×		US 2004022540 1 A1	20041111		Computer-implemented method and carrier medium configured to generate a set of process parameters and/or a list of potential causes of deviations for a lithography process	700/121		700/121
29	×		US 2004019928 2 A1	20041007		a afer, a afer, and adjusting of wafers	700/121		700/121

	33 ×	32 X	31 ×	30 ×	U 1
SII	US 2004014813 6 A1	US 2004016765 6 Al	US 2004017215 2 A1	US 2004018130 3 A1	Document ID
US	20040729	20040826	20040902	20040916	Issue Date
					Page s
alarm system	Management supporting apparatus, management supporting system, management supporting method, management supporting program, and a recording medium with the program recorded therein	Production managing system of semiconductor device	Sorting a group of integrated circuit devices for those devices requiring special testing	Relatively unique ID in integrated circuit	Title
700/110	702/188	700/121	700/121	700/115	Current OR
700/121	702/184			380/44 <b>;</b> 700/121	Current XRef
700/121	702/184	700/121	700/121	700/121	Retrieva 1 Classif

	G	Р			Page s	Title Configuration and method for detecting	Current	Current XRef
35	×		04011705 Al	20040617		uration and for detecting s on a ate in a sing tool	700/121	700/110
3	×		US 2004011117 6 A1	20040610		ion and of wafer order at	700/121	
37	×		US 2004010702 0 A1	20040603		tion system	700/121	
3 8	×		US 2004008807 1 Al	20040506		Aligner evaluation system, aligner evaluation method, a computer program product, and a method for manufacturing a semiconductor device	700/121	·
39	×		US 2004005945 20040325 6 A1	20040325			700/121	257/E21.5 25

	ď	Р	Document ID	Issue Date	Page s	Title	Current OR	Current XRef	Retrieva 1 Classif
40	×		US 2004003947 3 A1	20040226		Integrated circuit profile value determination	700/121		700/121
41	×		US 2004002902 9 Al	20040212		Error reduction in semiconductor processes	430/30	355/44; 355/52; 355/56; 430/22; 430/311; 700/121; 700/65; 702/122	700/121
42	×		US 2004001525 6 A1	20040122		Feedback method utilizing lithographic exposure field dimensions to predict process tool overlay settings	700/121	716/21	700/121
43	×		US 2004000640 4 A1	20040108		Permanent chip ID using FeRAM	700/115	700/121	700/121
44	×		US 2003023658 6 A1	20031225		Method for failure analysis and system for failure analysis	700/110	700/121	700/121

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			SU			Method and system for estimating		
45	×		03022547 A1	20031204		roelectronic rication product ld	700/121	700/108
46	×		US 2003022070 8 A1	20031127		Integrated equipment set for forming shallow trench isolation regions	700/121	438/690
			SD			Manufacturing method and apparatus to		
47	×		2003021734 3 A1	20031120		pe-hold	716/4	700/121
						METHOD FOR AUTOMATICALLY		
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48	×		2003021246 9 A1	20031113		SPECIFICATION IN A SEMICONDUCTOR	171/00/	700/110
						MANUFACTURING PROCESS		
49	$\times$		US 2003020005 6 A1	20031023		Semiconductor device analysis system	702/183	-
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50	× d	. р	Document ID US 2003019910 8 A1	Issue Date 20031023	Page s	Method of monitoring and/or controlling a semiconductor manufacturing apparatus and a system therefor Method for using data regarding	Д 47	Current OR 438/14	4
51	×		US 2003019155 0 A1	20031009		regarding regarding facturing edures grated circs) have rgone, such irs, to sel edures the edures the tional repational repa	ing g rcuits ch as elect e IC's as pairs		rs C's
	×		US 2003018753 5 A1	20031002		Throughput analys: system and method	is	is 700/108	
<u>ა</u>	×		US 2003018207 9 A1	20030925		System and method provide measurement capabilities for both single-ended and differential signals with software switching	nt g	to nt 702/177	0

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	ď	ш	Document ID	Issue Date	Page s	Title	Current OR	Current XRef	l Classif
54	× .		US 2003017189 6 A1	20030911		Method and system for graphical evaluation of IDDQ measurements	702/183		702/183
						Semiconductor manufacturing			
л л	<		US	000000000000000000000000000000000000000	カ い	paratus ponent	700 / 108	702/182;	700/108;
Ċ	. >					management apparatus therefor, and			702/187
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						transport apparatus			
						Semiconductor			
			US			manufacturing			700/108
56	×	•	2003016321	20030828		apparatus and its	700/108	700/121	700/100,
			7 A1			diagnosis apparatus and operating system			, , ,
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		·	US			diagnosing life of			
57	×		2003015405	20030814			702/184		702/184
			2 A1			equipment using			
		_				rotary machine			

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US 2003013529 20030717 5 A1	US 2003013983 20030724 9 A1	US 2003014954 7 A1	US 2003015399 5 Al	Document ID
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Defect source identifier with static manufacturing execution system	Method of sorting a group of integrated circuit devices for those devices requiring special testing	Method for diagnosing failure of a manufacturing apparatus and a failure diagnosis system	Semiconductor manufacturing system and control method thereof	Title
700/108	700/115	702/183	700/101	Current OR
700/109; 700/110; 700/117; 700/121	700/109; 700/116; 700/121		700/121	Current XRef
700/108; 700/117; 700/121	700/121	702/183	700/121	Retrieva 1 Classif

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US 2003006091 6 A1	US 2003006548 4 A1	US 2003010097 0 Al	US 2003010554 7 A1	US 2003010994 5 A1	1 Document
20030327	20030403	20030529	20030605	20030612	Issue Date
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Automatic production quality control method and system	AC defect detection and failure avoidance power up and diagnostic system	Method and system of monitoring apparatuses of manufacturing IC	SYSTEM AND METHOD FOR MODIFYING ENCLOSED AREAS FOR ION BEAM AND LASER BEAM BIAS EFFECTS	Apparatus and method for automatically controlling semiconductor manufacturing process in semiconductor factory automation system	Title
700/121	702/187	700/108	700/121	700/95	Current OR
700/109		700/109; 700/121	438/4	700/109; 700/121	Current XRef
700/121	702/187	700/108; 700/121	700/121	700/121	Retrieva 1 Classif

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ļ	×		US 2003003730 9 A1	20030220		management managemend of iconduct		716/21	716/21 700/121
69	×		US 2003003304 6 A1	20030213	23	nd system facturing uctor	1	700/121	700/121 716/21
70	×		US 2003001840 6 A1	20030123	23	Method and system for manufacturing semiconductor devices		700/121	700/121 716/21
71	×		US 2003001414 6 A1	20030116		Dangerous process/pattern detection system and method, danger detection program, and semiconductor device manufacturing method	and ing	nd 700/121	

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US 2002014342 20021003 4 A1	US 2002016563 6 A1	US 2002018388 4 A1	US 2002019389 9 A1	US 2002019868 2·A1	US 2003001414 5 A1	Document ID
20021003	20021107	20021205	20021219	20021226	20030116	Issue Date
	24		18	8	18	Page s
Device and method of selecting photomask manufacturer based on received data	Systems and methods for metrology recipe and model generation	Method for continuous, non lot-based integrated circuit manufacturing	Dynamic metrology schemes and sampling schemes for advanced process control in semiconductor processing	Method and apparatus for determining end-point in a chamber cleaning process	Integration of fault detection with run-to-run control	Title
700/121	700/121	700/115	700/108	702/184	700/121	Current OR
		700/121	257/E21.5 25; 700/121; 700/97		700/108; 700/110	Current XRef
700/121	700/121	700/121	700/108; 700/121	702/184	700/108; 700/121	Retrieva 1 Classif

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78	× ·		us 2002012381 20020905 8 A1	20020905	_	Production managing system of semiconductor device	700/121		700/121
79	×		US 2002011175 20020815 9 A1	20020815		Failure analysis device and failure analysis method	702/82	700/108; 700/109; 700/110	700/108
80	×	_	US 2002010766 20020808 6 A1	20020808		Maintenance system for analyzing instrument	702/184		702/184
81	×		US 2002010356 4 A1	20020801		Methods and systems for determining a composition and a thickness of a specimen	700/121	·	700/121
82	×		US 2002010356 3 A1	20020801		Method of manufacturing a semiconductor device and manufacturing system	700/121		700/121

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US 2002006216 2 A1	US 2002006898 9 A1	US 2002007287 8 A1	US 2002008274 0 A1	Document ID
20020523	20020606	20020613	20020627	Issue Date
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User configurable multivariate time series reduction tool control method	Method and apparatus for designing integrated circuits and storage medium for storing the method	Deterioration diagnostic method and equipment thereof	Method for using data regarding manufacturing procedures integrated circuits (IC's) have undergone, such as repairs, to select procedures the IC's will undergo, such as additional repairs	Title
700/108	700/121	702/183	700/121	Current OR
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700/108	700/121	702/183	700/121	Retrieva 1 Classif

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87	×		US 2002005901 2 A1	20020516		Method of manufacturing semiconductor devices	700/121	257/E21.
88	$\times$	•	US 2002005901 0 A1	20020516		Failure analyzing device for semiconductors	700/110	257/E21. 25; 700/109; 700/117; 700/121
89	×		US 2002005580 1 A1	20020509		Fault detection and virtual sensor methods for tool fault monitoring	700/111	700/117; 700/175; 700/178
90	×		US 2002003544 7 A1	20020321	ω U	Remote diagnosing system for semiconductor manufacturing equipment and a remote diagnosing method	702/188	257 700 700 700 700
91	×		US 2002002625 1 A1	20020228		System and method for monitoring and controlling gas plasma processes	700/67	700/121; 700/68
92	×		US 2001005183 9 A1	20011213		DIFFERENTIAL PROCESS CONTROL METHOD	700/121	ļ. '

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